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March 22, 2006

To: Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572
28 Davis Avenue
Poughkeepsie, NY 12603

Subject: | Serial No. 10/660,914. 09/12/03 |

Chao-Peng Chen et al.

METHOD TO PRINT PHOTORESIST LINES
WITH NEGATIVE SIDEWALLS

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation In An Application.

The following Patents and/or Publications are submitted to comply with the duty
of disclosure under CFR 1.97-1.99 and 37 CFR 1.56.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States
Postal Service as first class mail in an envelope addressed to: Commissioner for Patents,
P.O. Box 1450, Alexandria, VA 22313-1450, on March 22, 2006.

Stephen B. Ackerman, Reg. # 37761

Signature/Date SB 3/22/06

Chemistry of a Chemically Amplified Negative Resist and Process Modification for Electron Beam Exposure, by Shigeki Yamamoto et al., Presented by Patrick Martens, Sumitomo Chemical America, discusses the chemistry of a chemically amplified negative resist and process modification for electron beam exposure.

Perpendicular Recording Head Technology, DASCOM Business Group, TDK Corporation , Japan, 07/23/02, p.5, discusses the ABS view of perpendicular head: Single Pole.

The paper “Bake Condition Effect on Hybrid Lithography Process for Negative Tone Chemically Amplified Resists,” by L. Pain et al., Advances in Resist Technology and Processing XVII, Francis M. Houlihan, Editor, Proceedings of SPIE, Vol. 3999 (2000), 0277-786X/00, presents the process optimization study of negative tone Chemically Amplified Resists (CAR) under E-Beam exposure.

Sincerely,



Stephen B. Ackerman,
Reg. No. 37761

Form PTO-1449 INFORMATION DISCLOSURE CITATION IN AN APPLICATION <i>(Use several sheets if necessary)</i>	Doctor Number (Optional) HTIRC-02-013	Application Number 10/660,914
	Applicant Chao - Peng Chen et al.	
	Filing Date 09/12/03	Drawn At U.S.

U. S. PATENT DOCUMENTS



FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Portion or Pages, Etc.)

- Chemistry of a Chemically Amplified Negative Resist and Process Modification for Electron Beam Exposure, by Shigeki Yamamoto et al., Presented by Patrick Martens, Sumitomo Chemical America.
- Perpendicular Recording Head Technology, DASCOM Business Group, TDK Corp., Japan, 07/23/02, p.5.

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

Form PTO-1449	Docket Number (Optional)	Application Number
INFORMATION DISCLOSURE CITATION IN AN APPLICATION	HTIRC-02-013	10/660,914
(Use several sheets if necessary)	Applicant	Chao - Peng Chen et al.
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